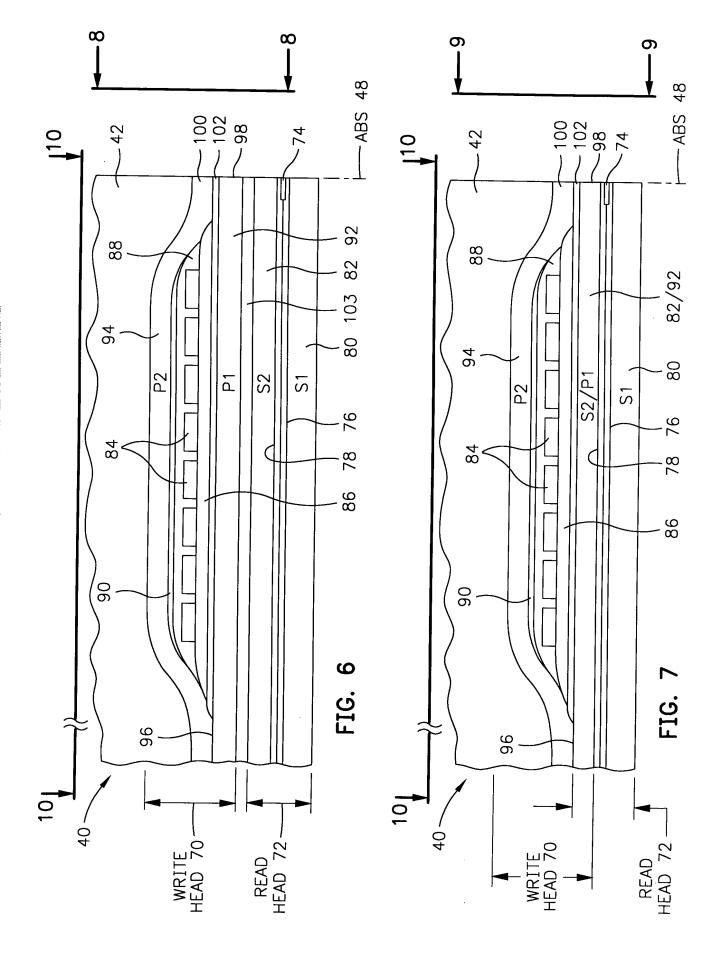
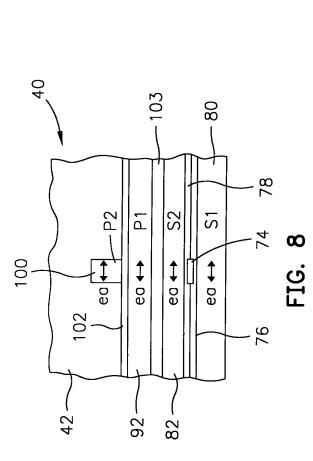
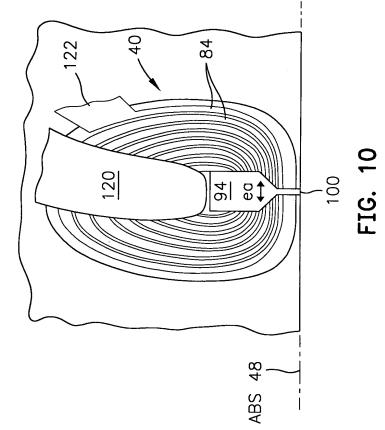


FIG. 5







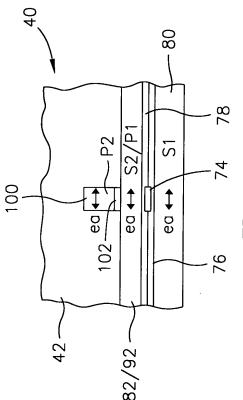
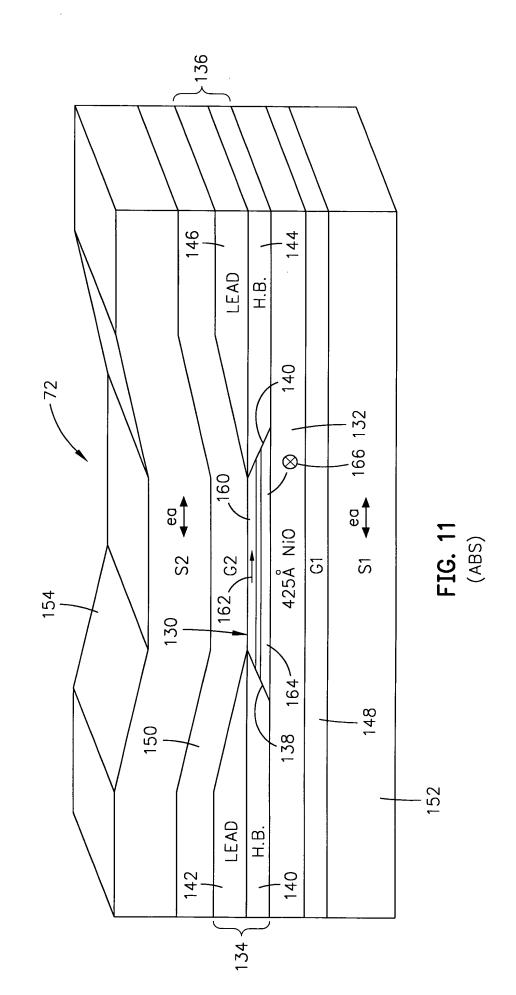
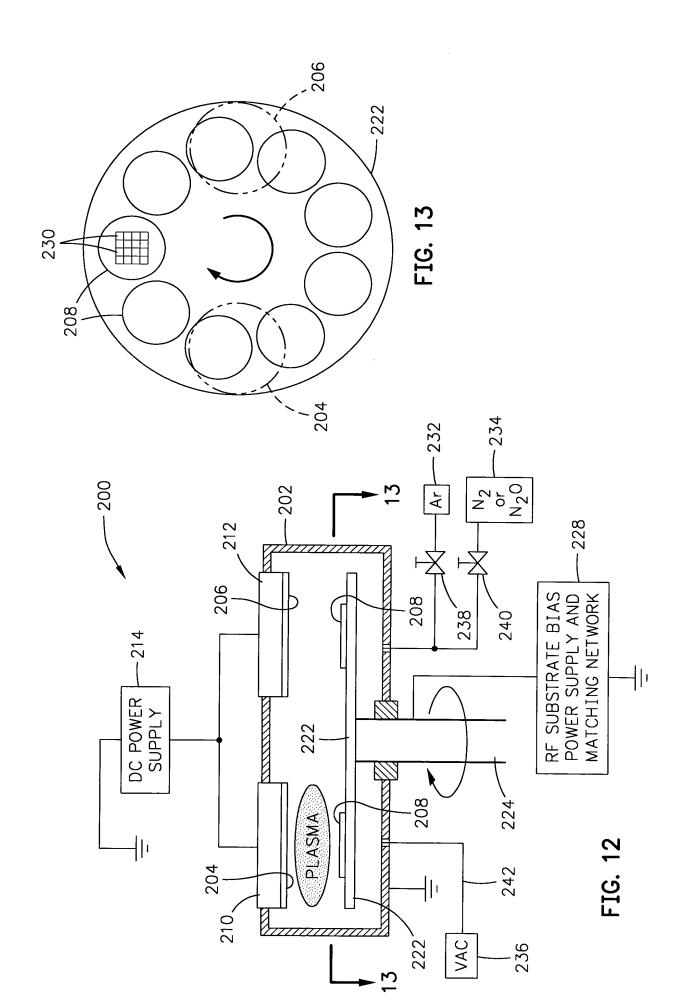


FIG. 9





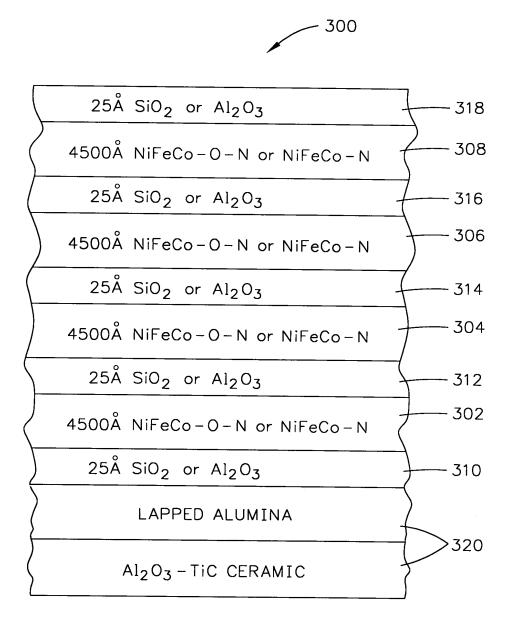
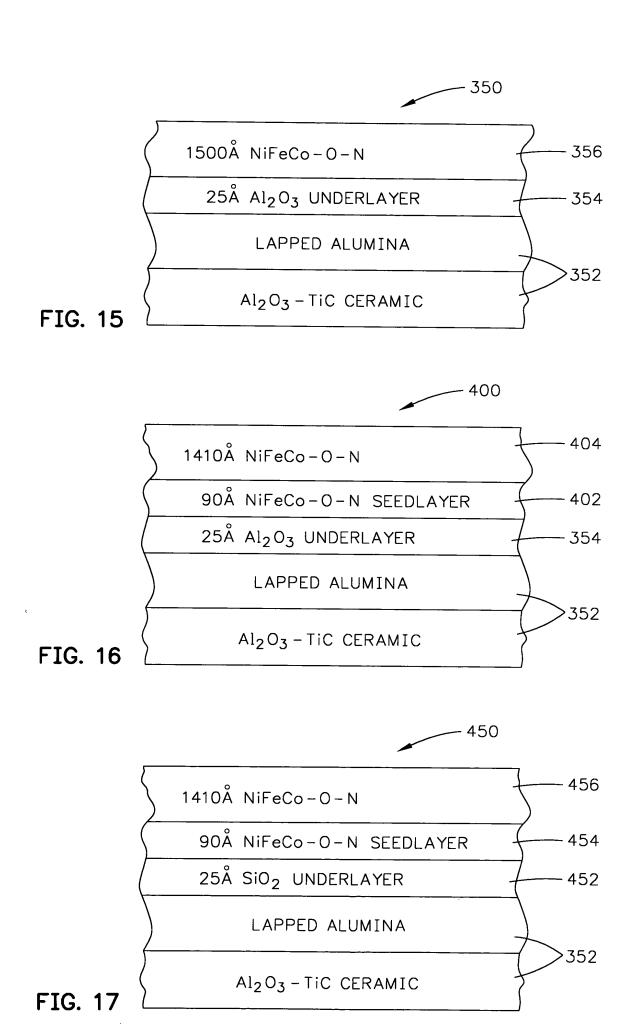
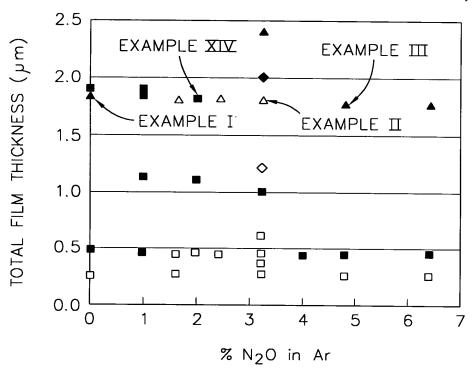


FIG. 14



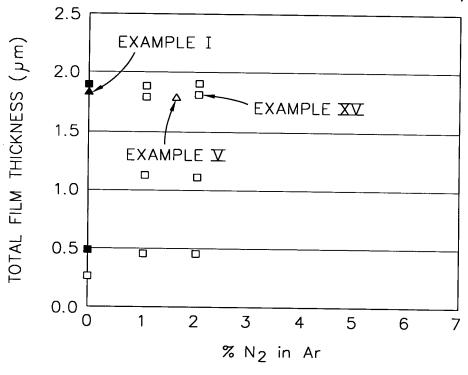
THICKNESS AND N₂O CONCENTRATION
DEPENDENCE OF IN-PLANE AND VERTICAL Hk IN
SINGLE LAYER AND LAMINATED NiFeCo-O-N FILMS
(DC MAG 1750 W, 2.0X10⁻³ mbar, NO BIAS)



- □ SINGLE LAYER FILMS IN PLANE Hk
- ♦ 2X LAMINATED FILMS IN PLANE Hk
- △ 4X LAMINATED FILMS-IN PLANE Hk
- SINGLE LAYER FILMS-VERTICAL Hk
- ◆ 2X LAMINATED FILMS-VERTICAL Hk
- ▲ 4X LAMINATED FILMS VERTICAL Hk

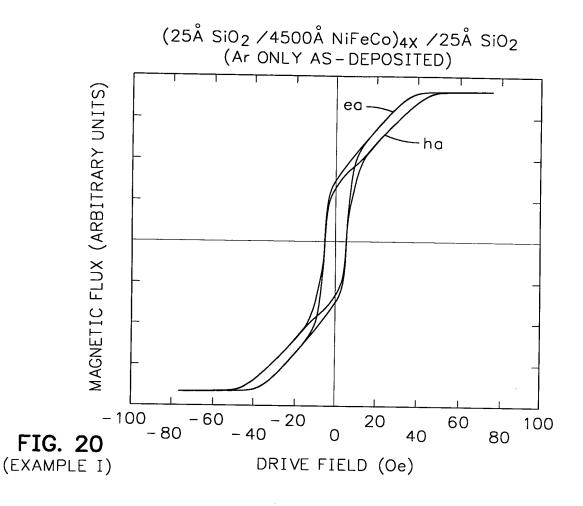
FIG. 18

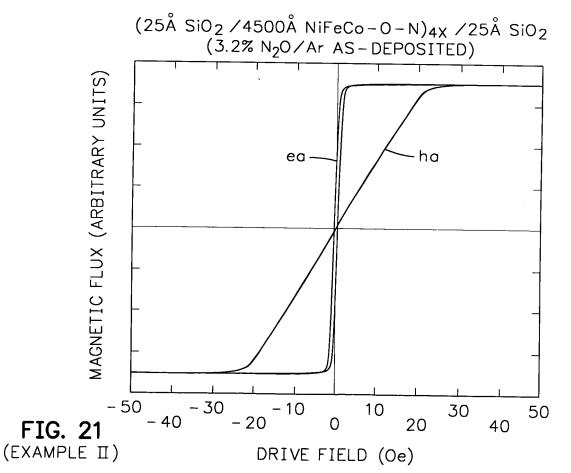
THICKNESS AND N₂ CONCENTRATION
DEPENDENCE OF IN-PLANE AND VERTICAL Hk IN
SINGLE LAYER AND LAMINATED NiFeCo-N FILMS
(DC MAG 1750 W, 2.0X10⁻³ mbar, NO BIAS)

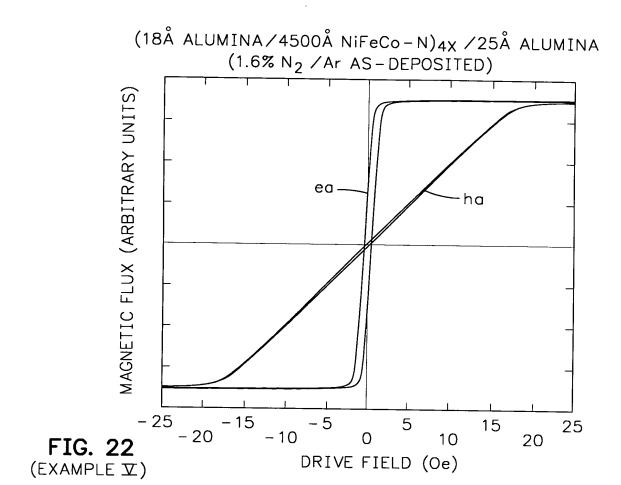


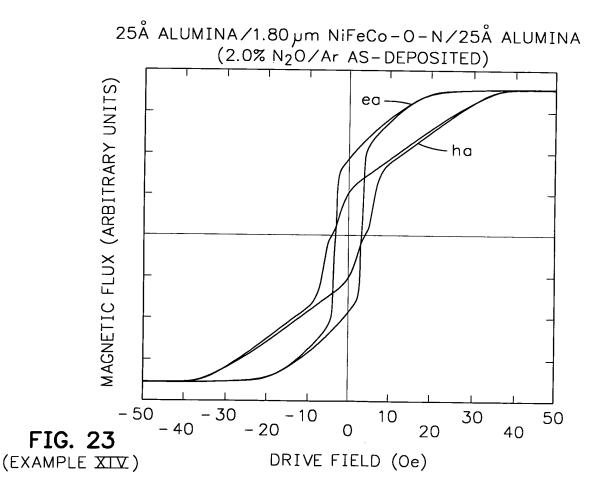
- □ SINGLE LAYER FILMS-IN PLANE HK
- △ 4X LAMINATED FILMS-IN PLANE HK
- SINGLE LAYER FILMS-VERTICAL Hk
- ▲ 4X LAMINATED FILMS VERTICAL Hk

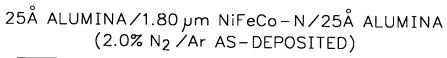
FIG. 19











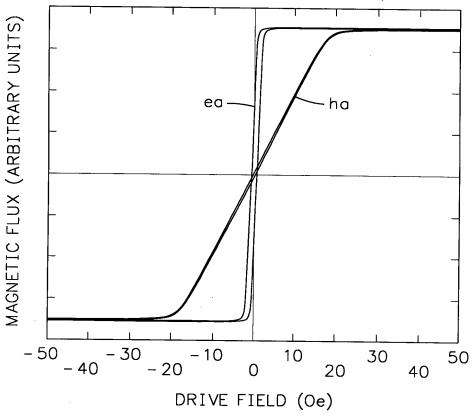
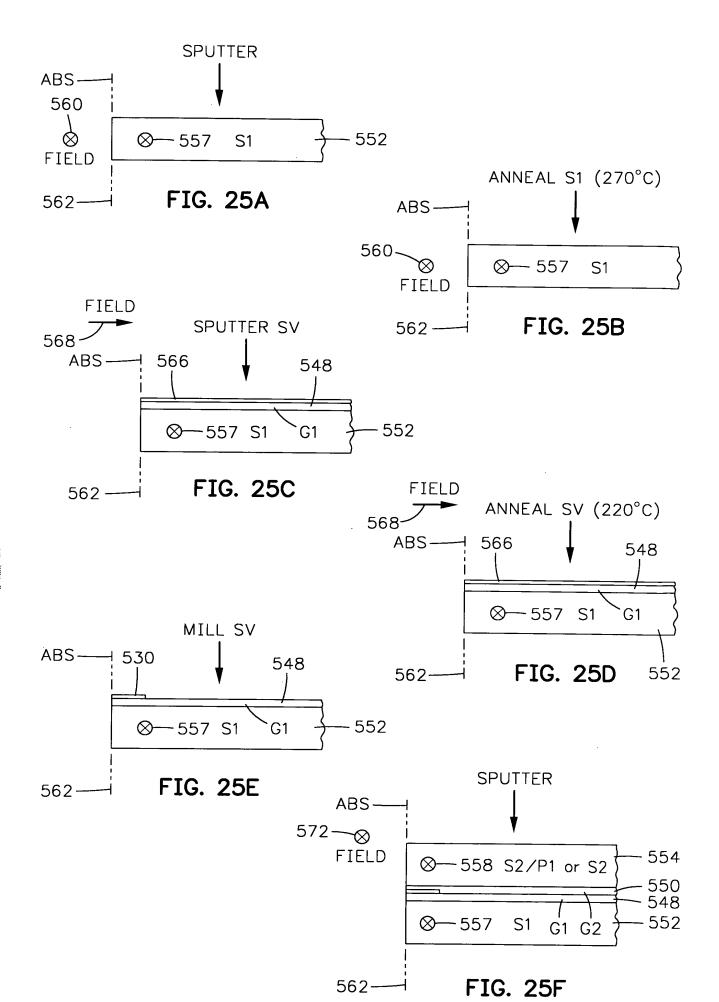
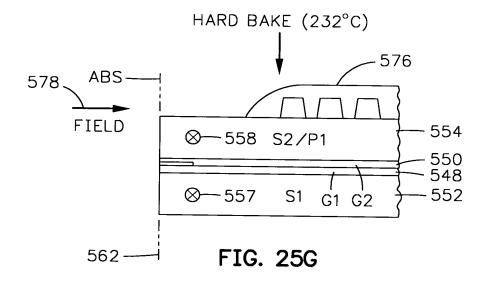
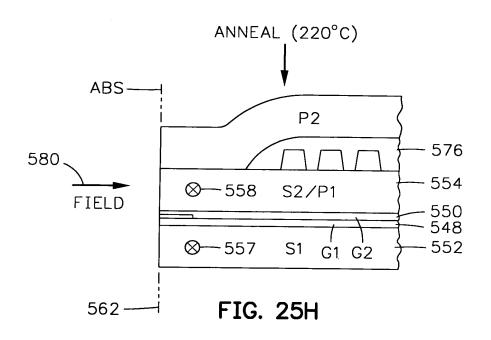
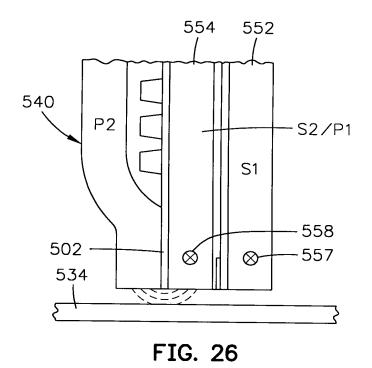


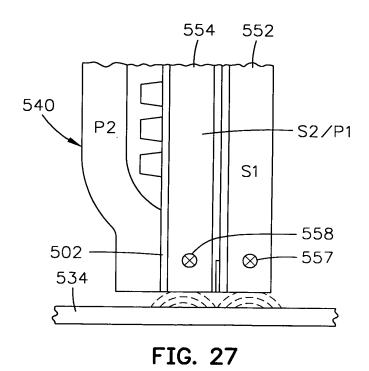
FIG. 24 (EXAMPLE XV)

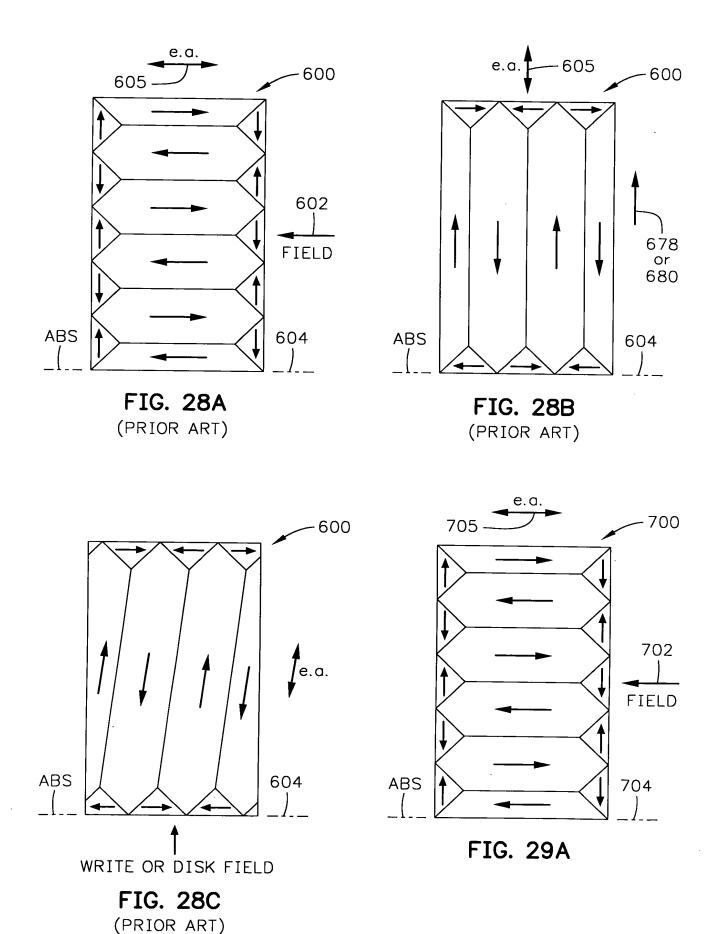












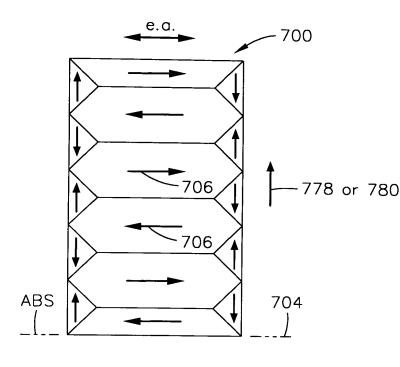


FIG. 29B
NiFeCo[-0]-N AFTER HARDBAKE
ANNEALING OR RESETTING

ANNEALING OR RESETTING
IN THE PRESENCE OF A FIELD
PERPENDICULAR TO THE ABS

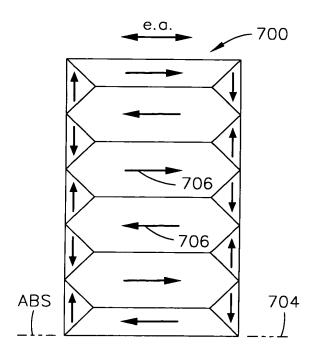


FIG. 29D

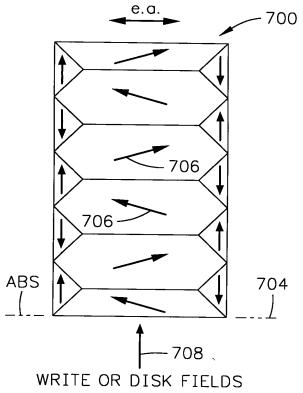


FIG. 29C